

ABSTRACT OF THE DISCLOSURE (FIG. 3)

"APPARATUS AND METHOD FOR SUPPLYING
PROCESS SOLUTION TO SURFACE OF SUBSTRATE
TO BE PROCESSED

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Disclosed is a processing apparatus comprising holding means, support means, process solution supply means, life means, and rotating means. A substrate to be processed is rotatably held by the holding means. An overhanging portion of the substrate extending over an edge of the holding means is supported by the support means to maintain a front surface of the substrate horizontally flat. A process solution is supplied from the process solution supply means onto the front surface of the substrate held by the holding means and supported by the support means. The substrate held by the holding means is vertically moved by the lift means relative to the support means. Further, the substrate moved upward relative to the support means is rotated by the rotating means.

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